

# Half Wavelength Contact Acoustic Microscopy (HaWaCAM): a novel metrology technique for semicon

P.L.M.J. van Neer<sup>1,2</sup>, B.A.J. Quesson<sup>1</sup>, M.S. Tamer<sup>3</sup>, K. Hatakeyama<sup>3</sup>, M.H. van Es<sup>3</sup>, M.C.J.M van Riel<sup>3</sup>, D. Piras<sup>3</sup>

<sup>1</sup>Department of Acoustics and Sonar, TNO, Oude Waalsdorperweg 63, 2597 AK the Hague, the Netherlands

<sup>2</sup>Medical Imaging, ImPhys, Lorentzweg 1, 2628 CJ, Delft University of Technology, the Netherlands

<sup>3</sup>Department of Optomechatronics, TNO, Stieltjesweg 1, 2628 CK Delft, the Netherlands

## I. Introduction

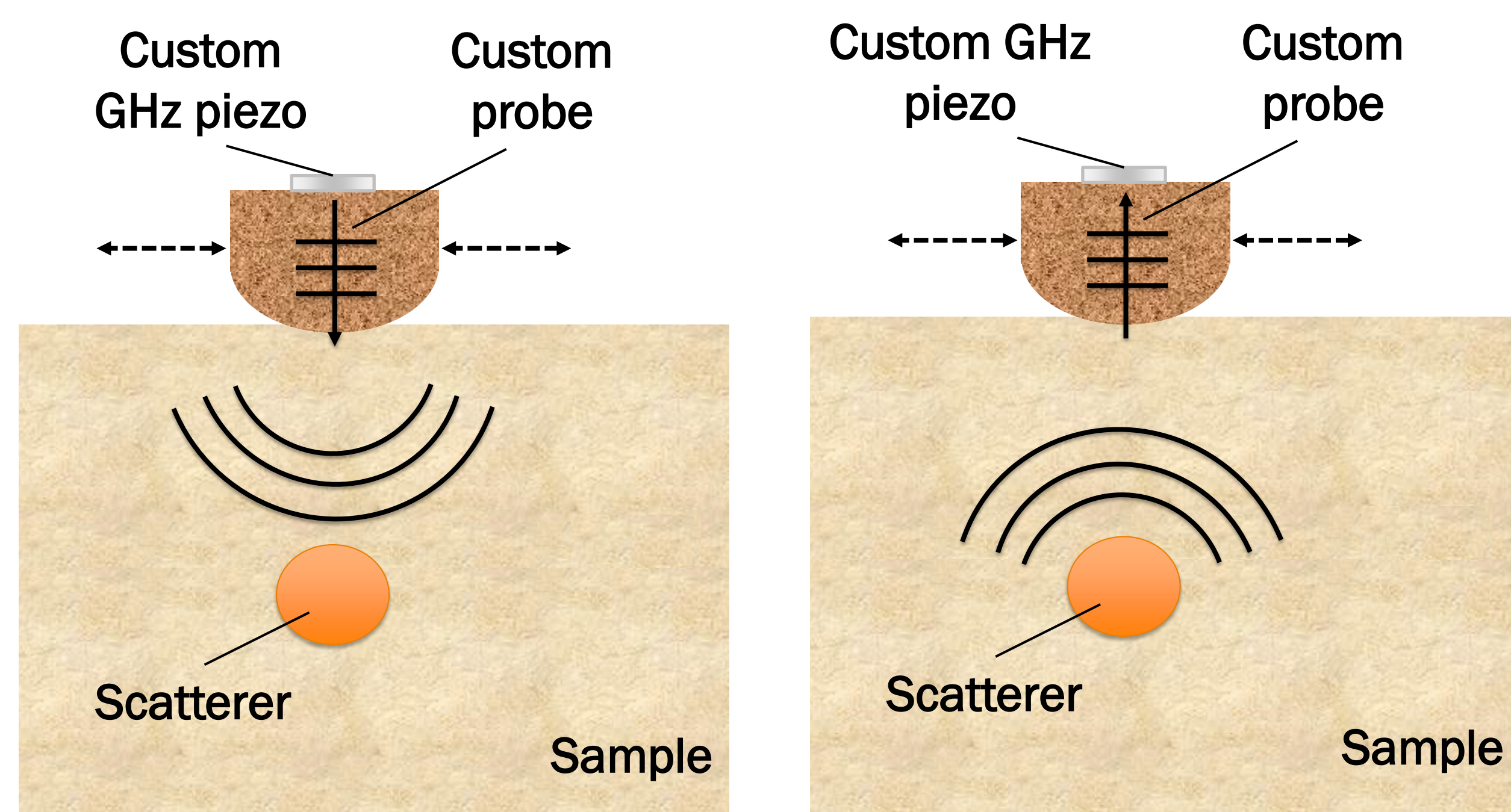
- Ever more functionality and processing power is integrated on the same semiconductor area.
  - To do so the device structures have become 3D,
  - and 3D NAND stack heights keep increasing.
- Cost effective device fabrication at high throughput requires metrology.
- The current non-destructive metrology workhorse for semicon is optics based.
- Optical metrology typically features 0.2 – 1.5  $\mu\text{m}$  resolution and is limited by:
  - optically opaque layers,
  - a low penetration depth ( $O(1 \mu\text{m})$ ).
- Acoustic microscopy may solve these limitations.
- However, its resolution is limited  $> O(3 \text{ (PMMA)} - 6 \text{ (SiO}_2\text{)} \mu\text{m})$  in samples
- Acoustic microscopy uses a geometric lens and a coupling liquid to couple the acoustic waves into the sample and to enable good lateral resolution [1].
- Acoustic frequency (resolution) limited by attenuation in coupling layer

## GOAL:

- To present a novel high frequency acoustic metrology technique entitled Half-Wavelength Contact Acoustic Microscopy (HaWaCAM), which does not require a liquid coupling layer.

## II. HaWaCAM measurement concept

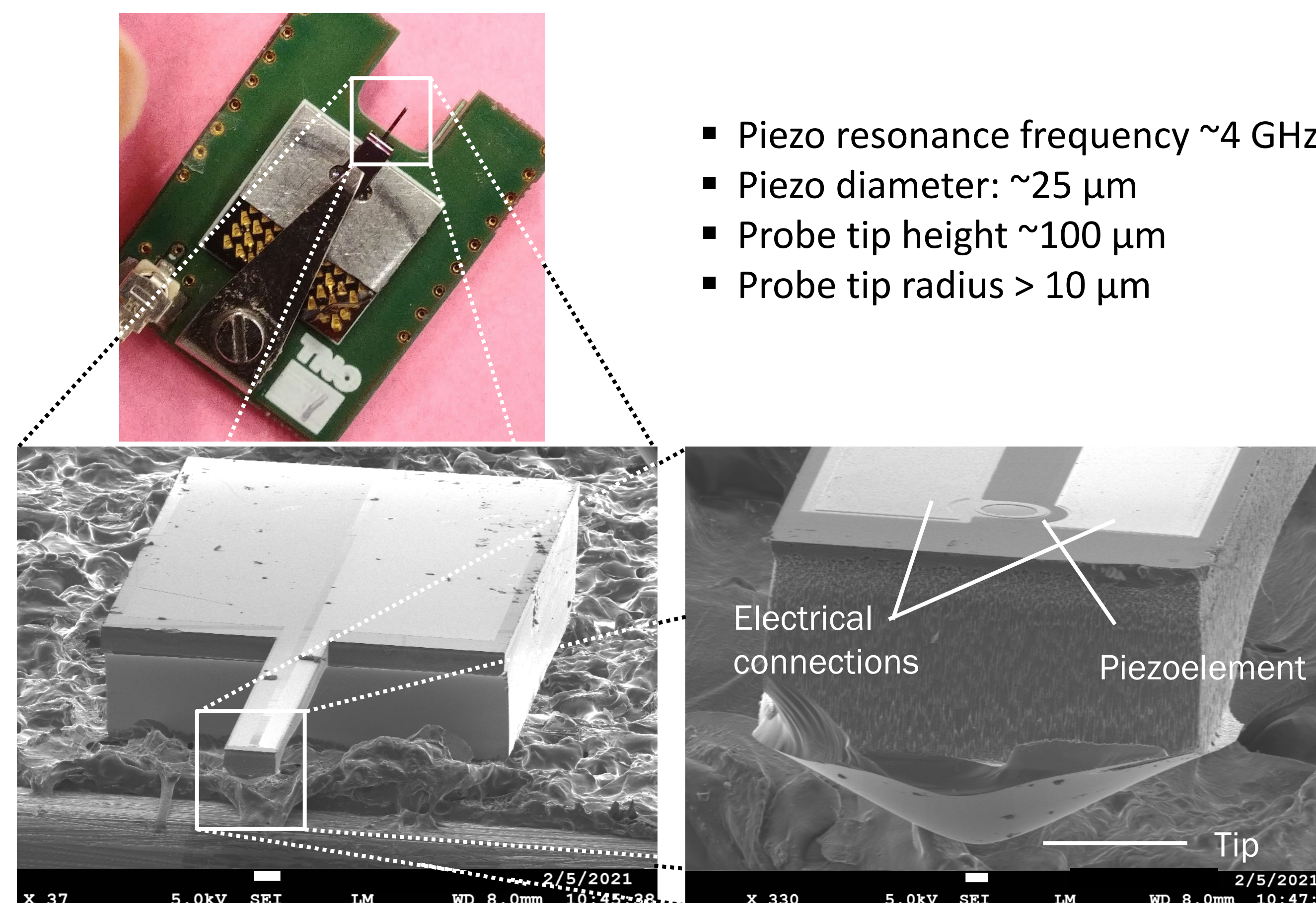
- HaWaCAM marries a probe with GHz piezotransducers
- Image contrast depends on acoustic impedance differences
- Tip – sample contact diameter  $\sim$  half wavelength
- Tip – sample contact: linear



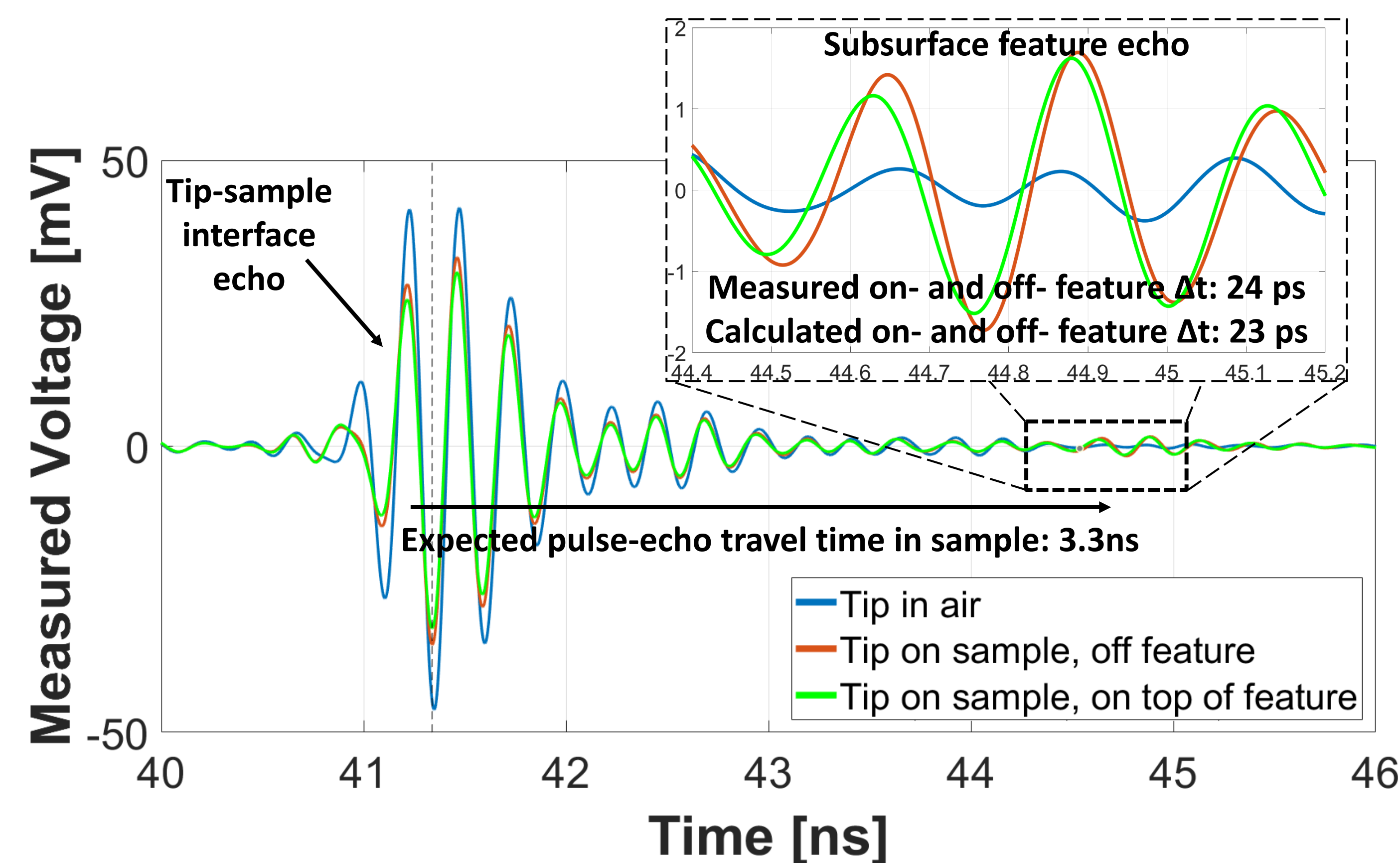
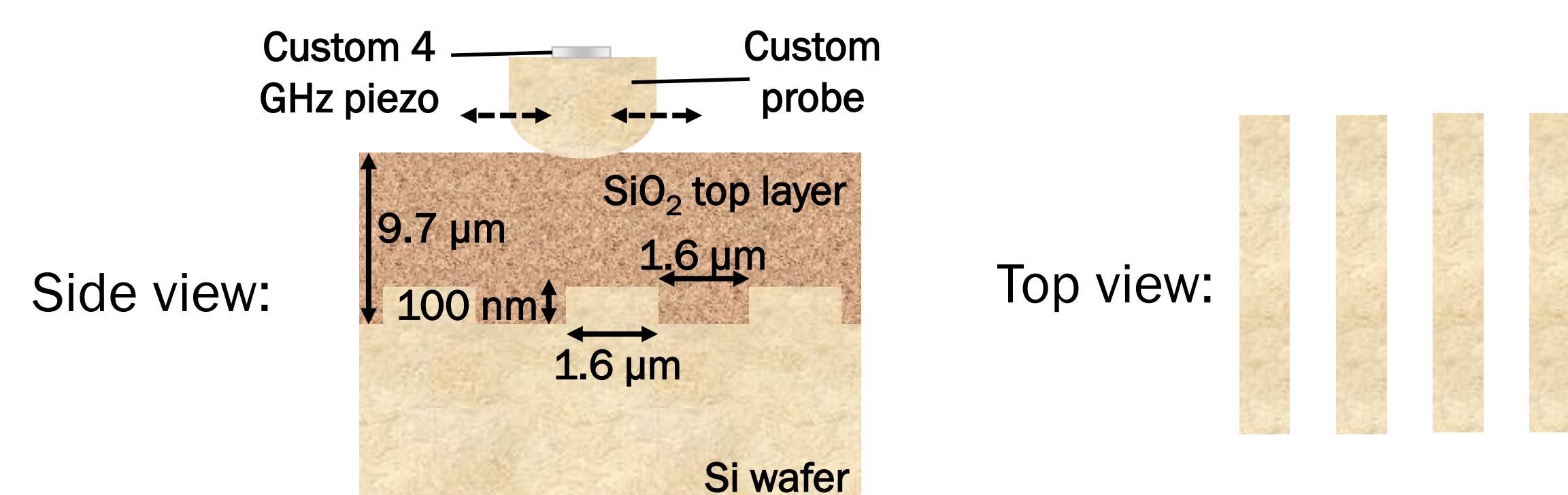
## HaWaCAM characteristics:

- No coupling layer (contact mode)
- Frequency  $>> 1 \text{ GHz} \rightarrow$  not limited by attenuation in coupling layer
- Currently implemented: 4 GHz – wavelength 0.75  $\mu\text{m}$  in PMMA, 1.5  $\mu\text{m}$  in SiO<sub>2</sub>
- Penetration  $O(10\text{s of } \mu\text{m})$
- Non-destructive/nondamaging
- Ability to image through opaque layers

## III. Custom GHz probe



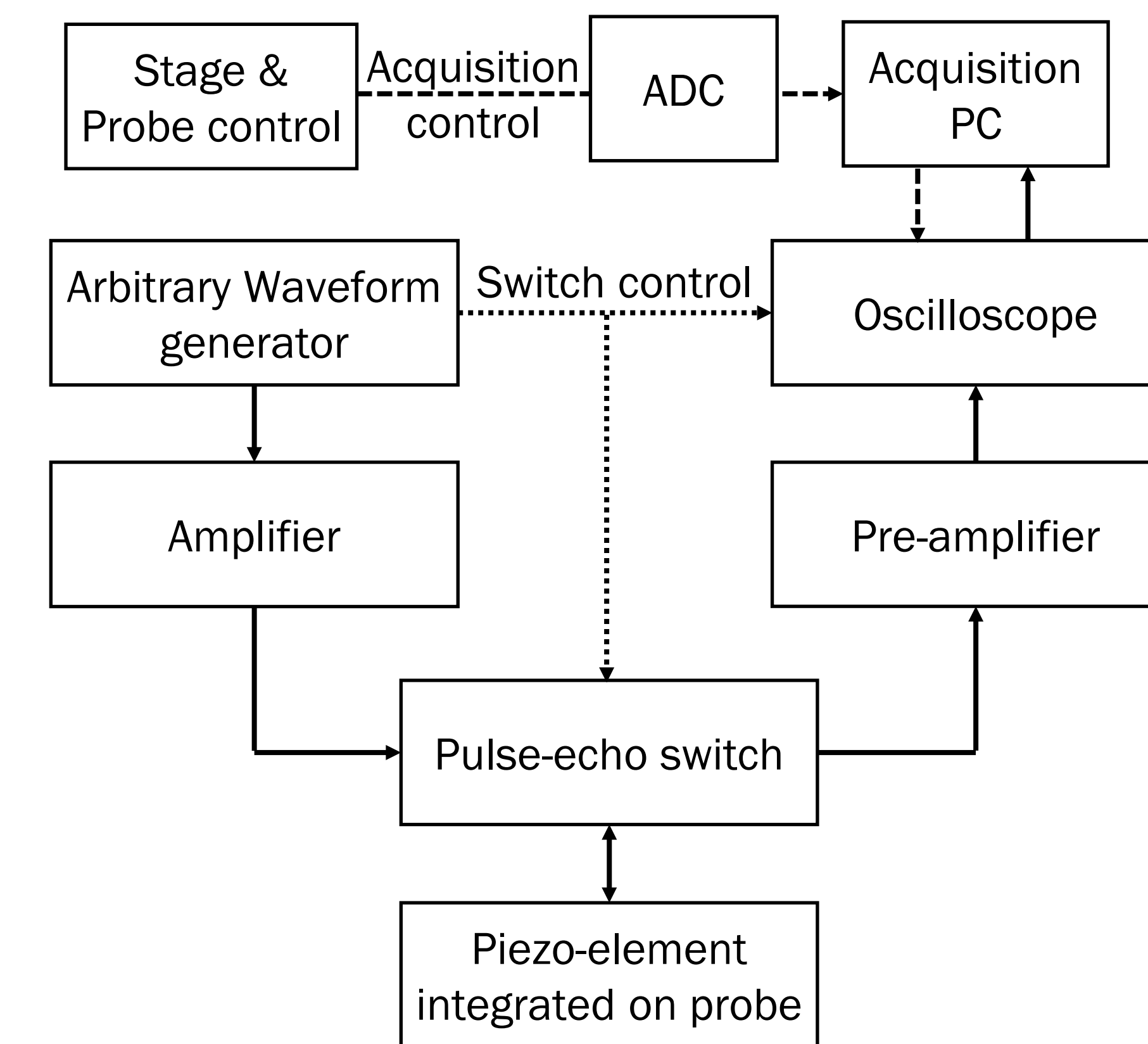
## V. Experimental results: linear grating buried below 9.7 $\mu\text{m}$ SiO<sub>2</sub>



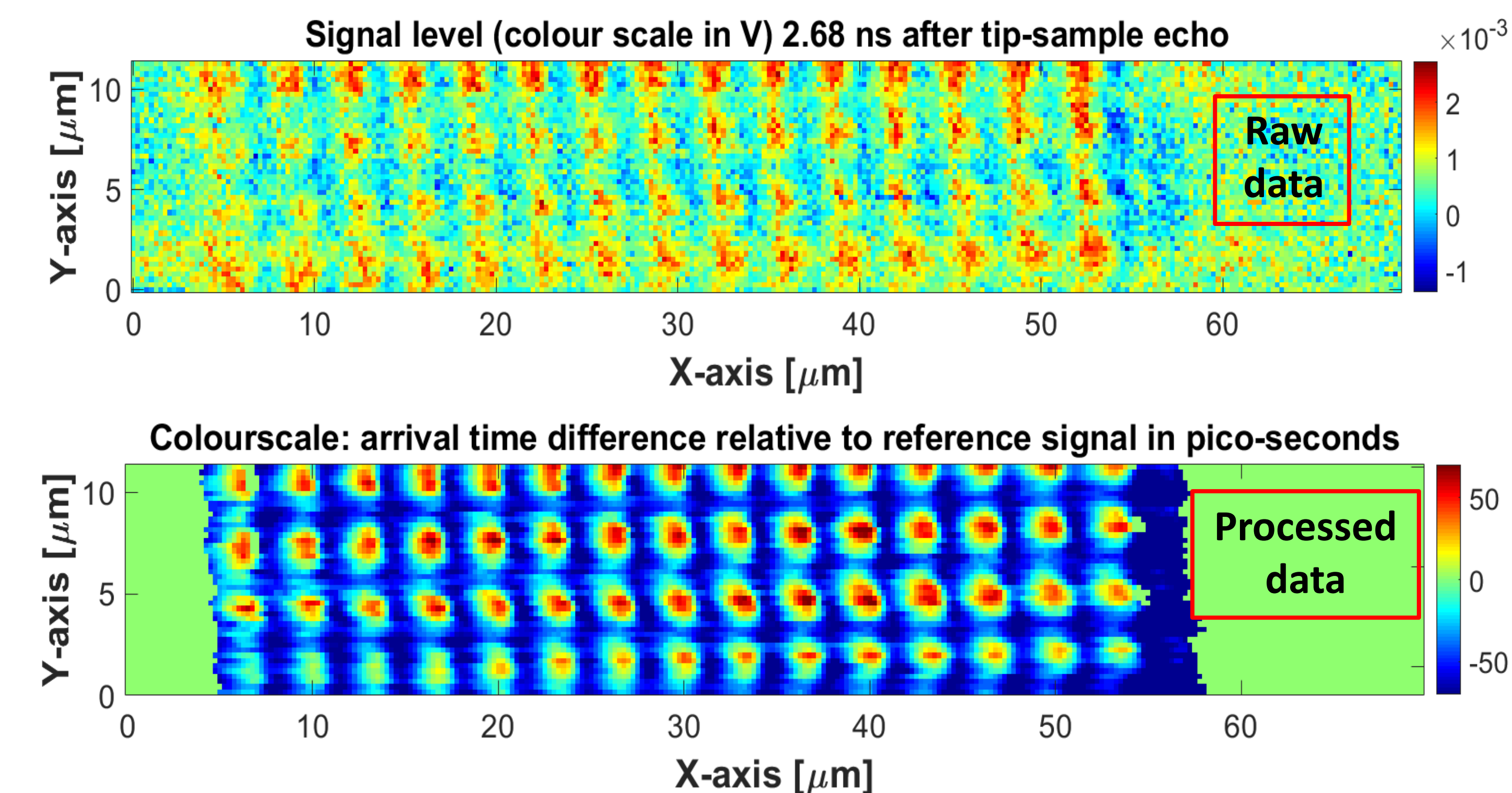
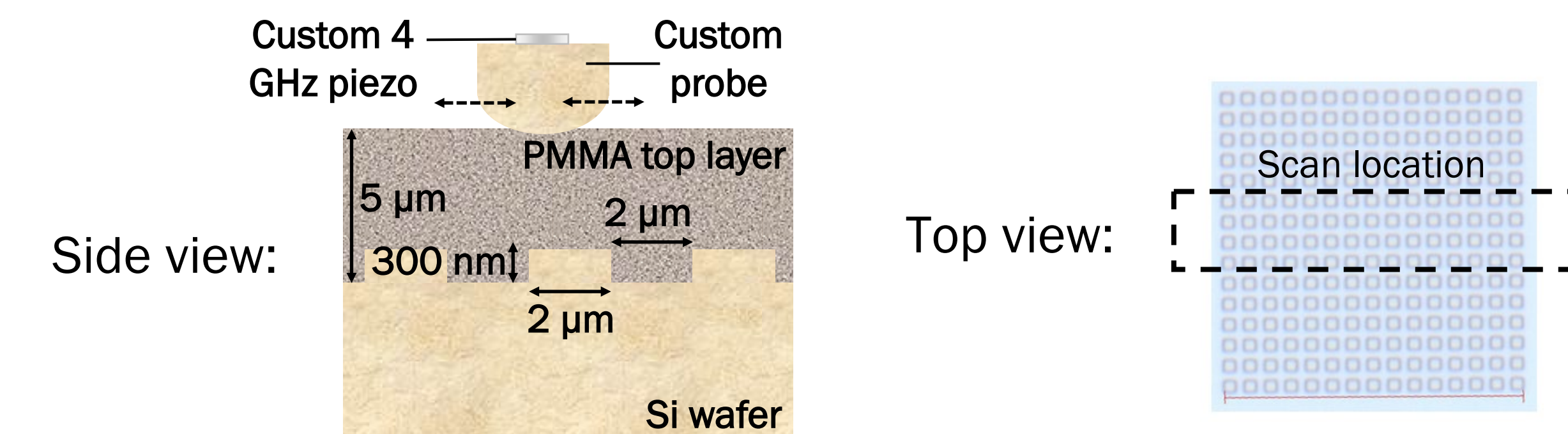
## References

- [1] Weiss, Lemor et al., IEEE Trans. Ultrason. Ferroelectr. Freq. Contr., 54(11), 2257-2271 (2007).

## IV. Experimental setup



## VI. Experimental results: matrix grating buried below 5 $\mu\text{m}$ PMMA



## VII. Discussion/Conclusion

- A novel high frequency acoustic metrology technique entitled Half-Wavelength Contact Acoustic Microscopy (HaWaCAM) was presented
- Current center frequency: 4 GHz, wavelength: 0.75  $\mu\text{m}$  (PMMA), 1.5  $\mu\text{m}$  (SiO<sub>2</sub>)
- Picosecond arrival time accuracy
- Current acoustic measurement time/point: 0.4 ms